

Abstract

On a substrate made of e.g., sapphire single crystal is formed an Al underlayer having a crystallinity of 90 seconds or below in FWHM of X-ray rocking curve. Then, on the AlN underlayer is formed a buffer layer having a composition of $Al_pGa_qIn_{1-p-q}N$ ($0 \le p \le 1$, $0 \le y \le q$), and on the buffer layer is formed a GaN-based semiconductor layer group.